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INFORMATION DISCLOSURE STATEMENT BY APPLICANT				ATTY. DOCKET NO. 071971-0643		SERIAL NO. 10/584,617					
(Substitute for form 1449/PTO)			APPLICANT Shunsaku MURAOKA, et al.								
			FILING DATE June 26, 2006								
			U	.S. PATENT	DOCUMENTS						
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1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.